L Number	Hits	Search Text	DB	Time stamp
1	44	((mass near2 (produc\$4 or manufactur\$4 or fabricat\$4 or making)) with	USPAT;	2004/09/17 10:30
		(before or prior) with (exposur\$3 or lithograph\$6 or photomask\$3 or photo-mask\$3 or resist or photo-resist or photolithograph\$6	US-PGPUB; EPO; JPO;	
		or stepper or photo-lithograph\$6)) and (photomask\$3 or photo-mask\$3	DERWENT;	
		or photoresist or photo-resist or ((mask\$3 or resist) with (photo or EUV	IBM_TDB	
		or UV or ultra-violet or light or DUV or excimer or lightsource or		
		photolithograph\$6 or photosensit\$6 or photo-lithograph\$6 or positive or		
		negative)))		
2	56	(mass near2 (produc\$4 or manufactur\$4 or fabricat\$4 or making)) with	USPAT;	2004/09/17 07:19
		(deposit\$4 or anneal\$5).clm.	US-PGPUB;	
			EPO; JPO; DERWENT;	
			IBM_TDB	
3	333	(mass near2 (produc\$4 or manufactur\$4 or fabricat\$4 or making)) with	USPAT;	2004/09/17 07:20
,	333	(deposit\$4 or anneal\$5) with (advantag\$5 or cost)	US-PGPUB;	
:		(depositor of different particular particula	ЕРО; ЈРО;	
			DERWENT;	
			IBM_TDB	0004/00/17/10 37
4	326	(mass adj2 (produc\$4 or manufactur\$4 or fabricat\$4 or making)) with	USPAT;	2004/09/17 10:31
		(deposit\$4 or anneal\$5) with (advantag\$5 or cost)	US-PGPUB;	
			EPO; JPO; DERWENT;	
			IBM TDB	
5	349136	700/\$.ccls. or 702/\$.ccls. or 438/\$.ccls. or 716/\$.ccls. or 430/\$.ccls.	USPAT;	2004/09/17 12:00
)	347130	700/4.0013. 01 702/4.0013. 01 130/4.0013. 01 710/4.0013.	US-PGPUB;	
			ЕРО; ЛРО;	
			DERWENT;	
			IBM_TDB	*******************
6	59	((mass adj2 (produc\$4 or manufactur\$4 or fabricat\$4 or making)) with	USPAT;	2004/09/17 07:21
		(deposit\$4 or anneal\$5) with (advantag\$5 or cost)) and (700/\$.ccls. or	US-PGPUB;	
		702/\$.ccls. or 438/\$.ccls. or 716/\$.ccls. or 430/\$.ccls.)	EPO; JPO; DERWENT;	
			IBM TDB	
20	24121	(photomask\$3 or photo-mask\$3 or mask\$3) near3 (type or kind or class)	USPAT;	2004/09/17 10:31
20	2 1121	(s) protonical to a protonical to a series (s) p	US-PGPUB;	
			ЕРО; ЈРО;	
			DERWENT;	
			IBM_TDB	2004/00/17 10 50
21	1577	(photomask\$3 or photo-mask\$3 or mask\$3) near3 (type or kind or	USPAT;	2004/09/17 10:58
		class).clm.	US-PGPUB; EPO; JPO;	
		·	DERWENT;	
			IBM_TDB	
22	873	(700/\$.ccls. or 702/\$.ccls. or 438/\$.ccls. or 716/\$.ccls. or 430/\$.ccls.)	USPAT;	2004/09/17 10:31
		and ((photomask\$3 or photo-mask\$3 or mask\$3) near3 (type or kind or	US-PGPUB;	
		class).clm.)	ЕРО; ЈРО;	
			DERWENT;	
			IBM_TDB	2004/00/17 10:33
23	473141	(mass adj2 (produc\$4 or manufactur\$4 or fabricat\$4 or making)) or	USPAT;	2004/09/17 10:32
		batch or lot	US-PGPUB; EPO; JPO;	
			DERWENT;	
			IBM TDB	
24	89	((700/\$.ccls. or 702/\$.ccls. or 438/\$.ccls. or 716/\$.ccls. or 430/\$.ccls.)	USPAT;	2004/09/17 10:40
		and ((photomask\$3 or photo-mask\$3 or mask\$3) near3 (type or kind or	US-PGPUB;	1
		class).clm.)) and ((mass adj2 (produc\$4 or manufactur\$4 or fabricat\$4	ЕРО; ЛРО;	
		or making)) or batch or lot)	DERWENT;	
			IBM_TDB	

05	1062	0.00000	TIODATE	0004/00/17 10 40
25	1063	257/390.ccls.	USPAT; US-PGPUB;	2004/09/17 10:40
1	}		EPO; JPO;	
1			DEDUELTO,	
}			DERWENT;	
26	50	267/200 1 1/ 1 1 1 1 1 1 1 1 1 1 1 1 1 1 1 1	BM_TDB	2004/00/17 10 42
26	58	257/390.ccls. and (organic or polymer or resin or polyimide or phenolic	USPAT;	2004/09/17 10:42
}	}	or acrylic)	US-PGPUB;	
			ЕРО; ЛРО;	
]			DERWENT,	
			IBM_TDB	
27	25472	(photomask\$3 or photo-mask\$3 or mask\$3) near3 (type or kind or class	USPAT;	2004/09/17 10:59
(1	or (metal and (organic or polymer or resin or polyimide or phenolic or	US-PGPUB;	
l	}	acrylic)))	ЕРО; ЛРО;	}
1	}		DERWENT;	
)	ļ		IBM_TDB	1
28	7786	(photomask\$3 or photo-mask\$3 or mask\$3) with (metal and (organic or	USPAT;	2004/09/17 12:04
(polymer or resin or polyimide or phenolic or acrylic))	US-PGPUB;	
1			ЕРО; ЛРО;	
}	}		DERWENT;	
ļ	ļ		IBM_TDB	
29	307	((photomask\$3 or photo-mask\$3 or mask\$3) near3 (type or kind or class	USPAT;	2004/09/17 11:00
		or (metal and (organic or polymer or resin or polyimide or phenolic or	US-PGPUB;	
ſ	1	acrylic)))) and (345/\$.ccls.)	EPO; JPO;	
Į			DERWENT;	
}			IBM_TDB	
30	59	((photomask\$3 or photo-mask\$3 or mask\$3) with (metal and (organic or	USPAT;	2004/09/17 11:00
i		polymer or resin or polyimide or phenolic or acrylic))) and (345/\$.ccls.)	US-PGPUB;	
		1 ,	ЕРО; ЛРО;	
Ì			DERWENT;	
}	1		IBM_TDB	
31	1	(photomask\$3 or photo-mask\$3 or mask\$3) with (metal and (organic or	USPAT;	2004/09/17 12:31
• •	•	polymer or resin or polyimide or phenolic or acrylic)) with menu	US-PGPUB;	2001/09/17 12.31
		polymer or realit or polymine or phonone or derymoly with mond	EPO; JPO;	
1			DERWENT;	
(IBM TDB	
41	8	3767490.URPN.	USPAT	2004/09/17 11:23
45	48	216/49.ccls. and 216/51.ccls.	USPAT;	2004/09/17 11:59
.5		210/19,000. and 210/21.0019.	US-PGPUB;	2004/07/17 11:37
}	ŀ		ЕРО; ЛРО;	
	(DERWENT;	
			IBM_TDB	
46	1061	exposure with (ebeam or e-beam)	USPAT;	2004/09/17 11:59
.0	1001	exposure with (cocain of c-ocain)	US-PGPUB;	2004/03/17 11.33
ļ)			
			EPO; JPO; DERWENT;	
47	3002	exposure with (ebeam or e-beam or (energy near2 beam))	BM_TDB	2004/00/17 12:21
7,	3002	exposure with (cocam of c-ocam of (energy hearz beam))	USPAT;	2004/09/17 12:31
			-US-PGPUB;	
1			EPO; JPO;	
			DERWENT;	
10	361865	700/9 colo en 700/9 colo en 429/9 col = 71/49 cl = 429/9 cl	IBM_TDB	2004/00/27 22 01
48	201802	700/\$.ccls. or 702/\$.ccls. or 438/\$.ccls. or 716/\$.ccls. or 430/\$.ccls. or	USPAT;	2004/09/17 12:01
		216/\$.ccls.	US-PGPUB;	
			EPO; JPO;	
			DERWENT;	
40	FF	700/h 1 700/h 1 400/h	IBM_TDB	
49	556111	700/\$.ccls. or 702/\$.ccls. or 438/\$.ccls. or 716/\$.ccls. or 430/\$.ccls. or	USPAT;	2004/09/17 13:54
		216/\$.ccls. or 257/\$.ccls.	US-PGPUB;	
			EPO; JPO;	
			DERWENT;	
	L	<u></u>	IBM_TDB	

			Trap (m)	
50	303	382/144.ccls.	USPAT;	2004/09/17 12:03
			US-PGPUB;	
			ЕРО; ЈРО;	
			DERWENT;	
			IBM_TDB	
51	20	382/144.ccls. and (organic or polymer or resin or polyimide or phenolic	USPAT;	2004/09/17 13:00
		or acrylic)	US-PGPUB;	
			EPO; JPO;	
			DERWENT;	1
			IBM_TDB	
52	556260	(700/\$.ccls. or 702/\$.ccls. or 438/\$.ccls. or 716/\$.ccls. or 430/\$.ccls. or	USPAT;	2004/09/17 12:31
		216/\$.ccls. or 257/\$.ccls.) or 382/144.ccls.	US-PGPUB;	
			ЕРО; ЛРО;	
			DERWENT,	
			IBM_TDB	
53	1304	((700/\$.ccls. or 702/\$.ccls. or 438/\$.ccls. or 716/\$.ccls. or 430/\$.ccls. or	USPAT;	2004/09/17 12:31
		216/\$.ccls. or 257/\$.ccls.) or 382/144.ccls.) and (exposure with (ebeam	US-PGPUB;	
		or e-beam or (energy near2 beam)))	EPO; JPO;	
			DERWENT;	
			IBM_TDB	
54	77	(((700/\$.ccls. or 702/\$.ccls. or 438/\$.ccls. or 716/\$.ccls. or 430/\$.ccls. or	USPAT;	2004/09/17 12:58
		216/\$.ccls. or 257/\$.ccls.) or 382/144.ccls.) and (exposure with (ebeam	US-PGPUB;	
		or e-beam or (energy near2 beam)))) and ((photomask\$3 or	ЕРО; ЛРО;	
	1	photo-mask\$3 or mask\$3) with (metal and (organic or polymer or resin	DERWENT;	
		or polyimide or phenolic or acrylic)))	IBM_TDB	
55	318	((photomask\$3 or photo-mask\$3) near3 ((first and second) or	USPAT;	2004/09/17 13:50
		another)).clm.	US-PGPUB;	
		,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,,	ЕРО; ЈРО;	
ļ			DERWENT;	
			IBM_TDB	
56	261	((700/\$.ccls. or 702/\$.ccls. or 438/\$.ccls. or 716/\$.ccls. or 430/\$.ccls. or	USPAT;	2004/09/17 12:59
		216/\$.ccls. or 257/\$.ccls.) or 382/144.ccls.) and (((photomask\$3 or	US-PGPUB;	
1		photo-mask\$3) near3 ((first and second) or another)).clm.)	EPO; JPO;	
			DERWENT;	
			IBM_TDB	
57	82		USPAT;	2004/09/17 13:51
		216/\$.ccls. or 257/\$.ccls.) or 382/144.ccls.) and (((photomask\$3 or	US-PGPUB;	
ļ		photo-mask\$3) near3 ((first and second) or another)).clm.)) and (organic	ЕРО, ЈРО,	
1		or resin or polyimide or phenolic or acrylic)	DERWENT;	'
			IBM_TDB	
58	2818		USPAT;	2004/09/17 13:54
		or manufactur\$4 or fabricat\$4 or making)) or batch or lot)	US-PGPUB;	
			EPO; JPO;	
			DERWENT;	
			IBM_TDB	
59	286006	((organic or resin or polyimide or phenolic or acrylic) with	USPAT;	2004/09/17 15:35
		(photosensit\$5 or photolacquer or photo-lacquer or photo-lithograph\$6	US-PGPUB;	
		or photolithograph\$6 or expos\$4 or radiation or UV or EUV or shield\$4	ЕРО; ЈРО;	
		or block\$4 or sheild\$4))	DERWENT;	
			IBM_TDB	
60	310		USPAT;	2004/09/17 14:22
		subsequent or after) with ((mass adj2 (produc\$4 or manufactur\$4 or	US-PGPUB;	
		fabricat\$4 or making)) or batch or lot)	EPO; JPO;	
			DERWENT;	
			IBM_TDB	
61	33		USPAT;	2004/09/17 14:03
		(photosensit\$5 or photolacquer or photo-lacquer or photo-lithograph\$6	US-PGPUB;	
		or photolithograph\$6 or expos\$4 or radiation or UV or EUV or shield\$4	EPO; JPO;	
		or block\$4 or sheild\$4))) and ((photomask\$3 or photo-mask\$3 or	DERWENT;	
		mask\$3) with (before or prior or subsequent or after) with ((mass adj2	IBM_TDB	
		(produc\$4 or manufactur\$4 or fabricat\$4 or making)) or batch or lot))		<u> </u>

	14	((700/\$.ccls. or 702/\$.ccls. or 438/\$.ccls. or 716/\$.ccls. or 430/\$.ccls. or	USPAT,	2004/09/17 13:54
62	1	216/9 cole or 257/9 cole) or 382/144 cols.) and (((organic or result or	US-PGPUB;	
	1	polyimide or phenolic or acrylic) with (photosensit\$5 or photolacquer or	ЕРО; ЈРО;	
	1	photo-lacquer or photo-lithograph\$6 or photolithograph\$6 or expos\$4 or	DERWENT; IBM TDB	
		radiation or UV or EUV or shield\$4 or block\$4 or shelld\$4))) and	IBM_1DD	
		((photomask\$3 or photo-mask\$3 or mask\$3) with (before or prior or		
		subsequent or after) with ((mass adj2 (produc\$4 or manufactur\$4 or subsequent or after) with ((mass adj2 (produc\$4) or manufactur\$4)	1	
(2	10	fabricat\$4 or making)) or batch or lot))) ((((organic or resin or polyimide or phenolic or acrylic) with	USPAT;	2004/09/17 14:14
63	19	(photosensit\$5 or photolacquer or photo-lacquer or photo-innographso	US-PGPUB;	
		or photolithograph\$6 or expos\$4 or radiation or UV or EUV or shield\$4	EPO; JPO;	
	1	or block\$4 or sheild\$4))) and ((photomask\$3 or photo-mask\$3 or	DERWENT;	
		mask\$3) with (before or prior or subsequent or after) with ((mass adj2)	IBM_TDB	
	1	(produc\$4 or manufactur\$4 or fabricat\$4 or making)) or batch or lot)))		
		not (((700/\$.ccls. or 702/\$.ccls. or 438/\$.ccls. or 716/\$.ccls. or 716/\$.ccls. or		
	1	430/\$.ccls. or 216/\$.ccls. or 257/\$.ccls.) or 382/144.ccls.) and ((((organic or resin or polyimide or phenolic or acrylic) with		
	1	(photosensit\$5 or photolacquer or photo-lacquer or photo-lithographibo		
		or photolithograph\$6 or expos\$4 or radiation or UV or EUV or snield\$4		
		or block\$4 or sheild\$4))) and ((photomask\$3 or photo-mask\$3 or		
		mask\$3) with (before or prior or subsequent or after) with ((mass adj2)		
		(produc\$4 or manufactur\$4 or fabricat\$4 or making)) or batch or lot))))	USPAT;	2004/09/17 15:27
65	273	(photomask\$3 or photo-mask\$3 or mask\$3) with ((batch or lot) near2	US-PGPUB;	200 (10)
		(produc\$4 or manufactur\$4 or fabricat\$4 or making))	ЕРО; ЛРО;	
	[DERWENT;	
			IBM_TDB	***************************************
66	1119	(photomask\$3 or photo-mask\$3 or mask\$3) with (mass adj2 (produc\$4	USPAT;	2004/09/17 15:33
00		or manufactur\$4 or fabricat\$4 or making))	US-PGPUB; EPO; JPO;	
	· [DERWENT;	
			IBM TDB	
	1274	((photomask\$3 or photo-mask\$3 or mask\$3) with ((batch or lot) near2	USPAT;	2004/09/17 14:26
68	1374	(produc\$4 or manufactur\$4 or fabricat\$4 or making))) or ((photomask\$3	US-PGPUB;	
		or photo-mask\$3 or mask\$3) with (mass adj2 (produc\$4 or	ЕРО; ЛРО;	
	ļ	manufactur\$4 or fabricat\$4 or making)))	DERWENT;	
			IBM_TDB USPAT;	2004/09/17 14:37
69	181	(((organic or resin or polyimide or phenolic or acrylic) with	US-PGPUB;	200-11071711.57
	Ì	(photosensit\$5 or photolacquer or photo-lacquer or photo-lithograph\$6 or photolithograph\$6 or expos\$4 or radiation or UV or EUV or shield\$4	EPO; JPO;	
		or block\$4 or sheild\$4))) and (((photomask\$3 or photo-mask\$3 or	DERWENT,	
		mask\$3) with ((hatch or lot) near2 (produc\$4 or manufactur\$4 or	IBM_TDB	
		fabricat\$4 or making))) or ((photomask\$3 or photo-mask\$3 or mask\$3)		
i		with (mass adi2 (produc\$4 or manufactur\$4 or fabricat\$4 or making))))	HCDAT.	2004/09/17 14:37
70	91	((700/\$.ccls. or 702/\$.ccls. or 438/\$.ccls. or 716/\$.ccls. or 430/\$.ccls. or	USPAT; US-PGPUB;	2004/05/17 14.57
		216/\$.ccls. or 257/\$.ccls.) or 382/144.ccls.) and ((((organic or resin or	EPO; JPO;	
		polyimide or phenolic or acrylic) with (photosensit\$5 or photolacquer or photo-lacquer or photo-lithograph\$6 or photolithograph\$6 or expos\$4 or	DERWENT;	
	}	radiation or UV or EUV or shield\$4 or block\$4 or sheild\$4))) and	IBM_TDB	
		(((photomask\$3 or photo-mask\$3) with ((batch or lot) near2	_	
		(produc\$4 or manufactur\$4 or fabricat\$4 or making))) or ((photomask\$3		
		or photo-mask\$3 or mask\$3) with (mass adj2 (produc\$4 or		
		manufactur\$4 or fabricat\$4 or making)))))	HISDAT.	2004/09/17 15:34
71	321694	((organic or resin or polyimide or phenolic or acrylic) with	USPAT; US-PGPUB;	2004/03/17 13:34
		(photosensit\$5 or photolacquer or photo-lacquer or photo-lithograph\$6	EPO; JPO;	
1		or photolithograph\$6 or light or UV or EUV or shield\$4 or block\$4 or sheild\$4 or phototool\$3 or photo-tool\$3))	DERWENT;	
1	1	shenda4 of phototooda5 of photo-toola5))	IBM_TDB	

	170	/// Land Caracastic) with	USPAT;	2004/09/17 14:37
72	172	(((organic or resin or polyimide or phenolic or acrylic) with (photosensit\$5 or photolacquer or photo-lacquer or photo-lithograph\$6	US-PGPUB;	2004/09/17 14:37
		or photolithograph\$6 or light or UV or EUV or shield\$4 or block\$4 or	EPO; JPO;	
]		sheild\$4 or phototool\$3 or photo-tool\$3))) and (((photomask\$3 or	DERWENT;	
ļ		photo-mask\$3 or mask\$3) with ((batch or lot) near2 (produc\$4 or	IBM_TDB	
ļ		manufactur\$4 or fabricat\$4 or making))) or ((photomask\$3 or		
		photo-mask\$3 or mask\$3) with (mass adj2 (produc\$4 or manufactur\$4		
		or fabricat\$4 or making))))		
73	81	((700/\$.ccls. or 702/\$.ccls. or 438/\$.ccls. or 716/\$.ccls. or 430/\$.ccls. or	USPAT;	2004/09/17 14:37
		216/\$.ccls. or 257/\$.ccls.) or 382/144.ccls.) and ((((organic or resin or	US-PGPUB;	
1		polyimide or phenolic or acrylic) with (photosensit\$5 or photolacquer or	ЕРО; ЛРО;	
		photo-lacquer or photo-lithograph\$6 or photolithograph\$6 or light or UV	DERWENT;	
		or EUV or shield\$4 or block\$4 or sheild\$4 or phototool\$3 or	IBM_TDB	
		photo-tool\$3))) and (((photomask\$3 or photo-mask\$3 or mask\$3) with		
		((batch or lot) near2 (produc\$4 or manufactur\$4 or fabricat\$4 or		·
		making))) or ((photomask\$3 or photo-mask\$3 or mask\$3) with (mass adj2 (produc\$4 or manufactur\$4 or fabricat\$4 or making)))))		
74	2	20020042007.pn.	USPAT;	2004/09/17 15:21
/-	2	20020042007.pit.	US-PGPUB;	
			ЕРО; ЛРО;	
			DERWENT;	
			IBM_TDB	
76	5033	(before or prior or subsequent\$2) with ((batch or lot) near2 (produc\$4 or	USPAT;	2004/09/17 15:45
		manufactur\$4 or fabricat\$4 or process\$3))	US-PGPUB;	
			EPO; JPO; DERWENT;	
			IBM_TDB	
77	5007	(before or prior or subsequent\$2) with (mass adj2 (produc\$4 or	USPAT;	2004/09/17 15:44
' '	3007	manufactur\$4 or fabricat\$4 or process\$3))	US-PGPUB;	200 1107117 15000
		managed of the same of the sam	ЕРО; ЈРО;	
			DERWENT;	
			IBM_TDB	
78	10005	((before or prior or subsequent\$2) with ((batch or lot) near2 (produc\$4	USPAT;	2004/09/17 15:34
		or manufactur\$4 or fabricat\$4 or process\$3))) or ((before or prior or	US-PGPUB; EPO; JPO;	
		subsequent\$2) with (mass adj2 (produc\$4 or manufactur\$4 or fabricat\$4	DERWENT;	
	1	or process\$3)))	IBM_TDB	
79	3	(((before or prior or subsequent\$2) with ((batch or lot) near2 (produc\$4)	USPAT;	2004/09/17 15:46
		or manufactur\$4 or fabricat\$4 or process\$3))) or ((before or prior or	US-PGPUB,	
	İ	subsequent\$2) with (mass adj2 (produc\$4 or manufactur\$4 or fabricat\$4	ЕРО; ЛРО;	
		or process\$3)))) and ((organic or resin or polyimide or phenolic or	DERWENT;	
		acrylic) with (photomask\$3 or photo-mask\$3) with (block\$4 or sheild\$3	IBM_TDB	
80	22	or sheild\$3 or attenuat\$4 or absorb\$4))	USPAT;	2004/09/17 15:39
80	23	(((before or prior or subsequent\$2) with ((batch or lot) near2 (produc\$4 or manufactur\$4 or fabricat\$4 or process\$3))) or ((before or prior or	US-PGPUB;	2004107111 13.39
		subsequent\$2) with (mass adj2 (produc\$4 or manufactur\$4 or fabricat\$4	ЕРО; ЛРО;	
		or process\$3)))) and ((organic or resin or polyimide or phenolic or	DERWENT;	
		acrylic) with mask\$3 with (photosensit\$5 or photolacquer or	IBM_TDB	
		photo-lacquer or photo-lithograph\$6 or photolithograph\$6 or UV or		
		EUV or shield\$4 or block\$4 or sheild\$4 or attenuat\$4 or absorb\$4))		
81	51	(before or prior or subsequent\$2) with (mass adj2 (produc\$4 or	USPAT;	2004/09/17 15:45
		manufactur\$4 or fabricat\$4 or process\$3)) with (photomask\$3 or	US-PGPUB;	
		photo-mask\$3 or mask\$3 or photoresist or photo-resist)	EPO; JPO; DERWENT;	
			IBM TDB	
82	42	(before or prior or subsequent\$2) with ((batch or lot) near2 (produc\$4 or	USPAT;	2004/09/17 15:45
	.2	manufactur\$4 or fabricat\$4 or process\$3)) with (photomask\$3 or	US-PGPUB;	
		photo-mask\$3 or mask\$3 or photoresist or photo-resist)	ЕРО, ЈРО;	
			DERWENT;	
			IBM_TDB	

			TIONAN	-00 1/00 to # 4 5 1 5
83	93	((before or prior or subsequent\$2) with (mass adj2 (produc\$4 or manufactur\$4 or fabricat\$4 or process\$3)) with (photomask\$3 or	USPAT; US-PGPUB;	2004/09/17 15:45
		photo-mask\$3 or mask\$3 or photoresist or photo-resist)) or ((before or	EPO; JPO;	
		prior or subsequent\$2) with ((batch or lot) near2 (produc\$4 or	DERWENT;	
		manufactur\$4 or fabricat\$4 or process\$3)) with (photomask\$3 or	IBM TDB	
		photo-mask\$3 or mask\$3 or photoresist or photo-resist))	_	
84	23	(((before or prior or subsequent\$2) with (mass adj2 (produc\$4 or	USPAT;	2004/09/17 15:46
J-1	23	manufactur\$4 or fabricat\$4 or process\$3)) with (photomask\$3 or	US-PGPUB;	
		photo-mask\$3 or mask\$3 or photoresist or photo-resist)) or ((before or	EPO; JPO;	
		prior or subsequent\$2) with ((batch or lot) near2 (produc\$4 or	DERWENT;	
		manufactur\$4 or fabricat\$4 or process\$3)) with (photomask\$3 or	IBM_TDB	
		photo-mask\$3 or mask\$3 or photoresist or photo-resist))) and (organic or		
		resin or polyimide or phenolic or acrylic)		
35	14	((((before or prior or subsequent\$2) with (mass adj2 (produc\$4 or	USPAT;	2004/09/17 15:51
-		manufactur\$4 or fabricat\$4 or process\$3)) with (photomask\$3 or	US-PGPUB;	
		photo-mask\$3 or mask\$3 or photoresist or photo-resist)) or ((before or	ЕРО; ЛРО;	
		prior or subsequent\$2) with ((batch or lot) near2 (produc\$4 or	DERWENT;	
		manufactur\$4 or fabricat\$4 or process\$3)) with (photomask\$3 or	IBM_TDB	
		photo-mask\$3 or mask\$3 or photoresist or photo-resist))) and (organic or		
		resin or polyimide or phenolic or acrylic)) and ((700/\$.ccls. or		
		702/\$.ccls. or 438/\$.ccls. or 716/\$.ccls. or 430/\$.ccls. or 216/\$.ccls. or		
		257/\$.ccls.) or 382/144.ccls.)		
6	0	(((((before or prior or subsequent\$2) with (mass adj2 (produc\$4 or	USPAT;	2004/09/17 15:51
		manufactur\$4 or fabricat\$4 or process\$3)) with (photomask\$3 or	US-PGPUB;	
		photo-mask\$3 or mask\$3 or photoresist or photo-resist)) or ((before or	ЕРО; ЛРО;	
		prior or subsequent\$2) with ((batch or lot) near2 (produc\$4 or	DERWENT;	
		manufactur\$4 or fabricat\$4 or process\$3)) with (photomask\$3 or	IBM_TDB	
		photo-mask\$3 or mask\$3 or photoresist or photo-resist))) and (organic or		
		resin or polyimide or phenolic or acrylic)) and ((700/\$.ccls. or		
		702/\$.ccls. or 438/\$.ccls. or 716/\$.ccls. or 430/\$.ccls. or 216/\$.ccls. or		
	1	257/\$.ccls.) or 382/144.ccls.)) not ((((before or prior or subsequent\$2)		
	ļ	with (mass adj2 (produc\$4 or manufactur\$4 or fabricat\$4 or process\$3))		
	l l	with (photomask\$3 or photo-mask\$3 or mask\$3 or photoresist or		
		photo-resist)) or ((before or prior or subsequent\$2) with ((batch or lot)		
		near2 (produc\$4 or manufactur\$4 or fabricat\$4 or process\$3)) with		
		(photomask\$3 or photo-mask\$3 or mask\$3 or photoresist or		
		photo-resist))) and (organic or resin or polyimide or phenolic or acrylic))		
37	9	((((before or prior or subsequent\$2) with (mass adj2 (produc\$4 or	USPAT;	2004/09/17 15:51
		manufactur\$4 or fabricat\$4 or process\$3)) with (photomask\$3 or	US-PGPUB;	
		photo-mask\$3 or mask\$3 or photoresist or photo-resist)) or ((before or	ЕРО; ЈРО;	
		prior or subsequent\$2) with ((batch or lot) near2 (produc\$4 or	DERWENT;	
		manufactur\$4 or fabricat\$4 or process\$3)) with (photomask\$3 or	IBM_TDB	
		photo-mask\$3 or mask\$3 or photoresist or photo-resist))) and (organic or		
		resin or polyimide or phenolic or acrylic)) not (((((before or prior or		
		subsequent\$2) with (mass adj2 (produc\$4 or manufactur\$4 or fabricat\$4		
		or process\$3)) with (photomask\$3 or photo-mask\$3 or mask\$3 or		
		photoresist or photo-resist)) or ((before or prior or subsequent\$2) with		
		((batch or lot) near2 (produc\$4 or manufactur\$4 or fabricat\$4 or		
		process\$3)) with (photomask\$3 or photo-mask\$3 or mask\$3 or		
		photoresist or photo-resist))) and (organic or resin or polyimide or		
		phenolic or acrylic)) and ((700/\$.ccls. or 702/\$.ccls. or 438/\$.ccls. or		
		716/\$.ccls. or 430/\$.ccls. or 216/\$.ccls. or 257/\$.ccls.) or 382/144.ccls.))	Tran . F	2004/00/21 20 20
-	1	20020042007.pn. and Rom and logic and cell	USPAT;	2004/08/31 20:30
	ļ		US-PGPUB;	
	1		ЕРО; ЈРО;	
			DERWENT;	
			IBM_TDB	2004/00/01 20 7
-	1	20020042007.pn. and Rom and logic and (unit near2 cell)	USPAT;	2004/08/31 20:54
			US-PGPUB;	
			ЕРО; ЈРО;	
			DERWENT;	
	1		IBM TDB	l

			,	
-	1	20020042007.pn. and photomask\$3 with amount	USPAT; US-PGPUB;	2004/08/31 20:54
]		ЕРО; ЛРО;	
	•		DERWENT,	
	}		IBM_TDB	
_	1	20020042007.pn. and (photomask\$3 with amount)	USPAT;	2004/08/31 20:55
] • !	20020042007.pit. and (photomask\$5 with amount)	US-PGPUB;	2004/06/31 20:33
	[EPO; JPO;	
	1		DERWENT;	
	}			
		(20020042007 16 42 - 42 - 44	IBM_TDB USPAT;	2004/09/21 21:02
-	1	20020042007.pn. and (exposur\$3 with amount)		2004/08/31 21:03
			US-PGPUB;	
	[EPO; JPO;	
	}		DERWENT;	
] _ ,	1 1 1 1 1 1 1 1 1 1 1 1 1 1 1 1 1 1 1	IBM_TDB	2004/00/21 21 04
-) 1)	20020042007.pn. and ((exposur\$3 or photomask\$3) with (amount or	USPAT;	2004/08/31 21:04
	1	[jud\$6))	US-PGPUB;	
!	1		ЕРО; ЛРО;	
	-		DERWENT;	
	}		IBM_TDB	
-	1	20020042007.pn. and ((exposur\$3 or photomask\$3) with (amount or	USPAT;	2004/08/31 21:04
		judg\$6))	US-PGPUB;	
	[ЕРО; ЛРО;	
1]		DERWENT;	{
	1		IBM_TDB	
-	1	20020042007.pn. and ((exposur\$3 or photomask\$3) same (amount or	USPAT;	2004/08/31 22:18
j	<u>'</u>	judg\$6))	US-PGPUB;	
ļ	!	()	ЕРО; ЈРО;	
			DERWENT;	
1			IBM_TDB	
1 -	1	20020042007.pn. and (prior).clm.	USPAT;	2004/08/31 21:52
1	,	200200 (2007.pit. and (prior).emi.	US-PGPUB;	200 (103/51 21:35
1			ЕРО; ЛРО;	
			DERWENT;	
	1		IBM_TDB	
_	1	20020042007.pn. and (prior)	USPAT;	2004/08/31 21:52
} -	1	20020042007.pm. and (prior)	US-PGPUB;	2004/00/31 21:32
)			EPO; JPO;	
			DERWENT;	
			IBM TDB	
	1	20020042007 pp. and (nattern\$4 with logic)	USPAT;	2004/08/31 22:20
_		20020042007.pn. and (pattern\$4 with logic)		2004/00/31 22.20
	1		US-PGPUB;	
j	1		EPO; JPO;	
			DERWENT;	
		20020042007 1 (IBM_TDB	2004/09/21 22 24
-	1	20020042007.pn. and (pattern\$4 same logic)	USPAT;	2004/08/31 22:24
l	}		US-PGPUB;	
{	1		EPO; JPO;	
	}		DERWENT;	
			IBM_TDB	
-	1	20020042007.pn. and (pattern\$4 same ROM)	USPAT;	2004/08/31 22:26
	1		US-PGPUB;	}
	1		ЕРО; ЈРО;	}
	}		DERWENT,	
			IBM_TDB	
-	1	20020042007.pn. and (menu same type)	USPĀT;	2004/08/31 22:26
	1	, , , , , , , , , , , , , , , , , , , ,	US-PGPUB;	(
	}		ЕРО; ЈРО;	{
)			DERWENT;	
i			IBM_TDB	
	<u></u>	1	1	1

			TYODAT	
-	1	20020042007.pn. and (energy near3 beam)	USPAT;	2004/08/31 22:27
			US-PGPUB;	
			ЕРО; ЛРО;	
			DERWENT;	
			IBM_TDB	
-	1	20020042007.pn. and (evaluat\$4 same predetermin\$7 same pattern\$4)	USPAT;	2004/08/31 22:30
		• •	US-PGPUB;	
			ЕРО; ЛРО;	
			DERWENT:	
			IBM_TDB	
	1	20020042007.pn. and (reproduc\$5)	USPAT;	2004/08/31 22:29
_	1	20020042007.pii. aila (Teproducas)	US-PGPUB;	200 1100/31 22:25
	1		EPO; JPO;	
			DERWENT;	
			IBM_TDB	************
-	1	20020042007.pn. and (differ\$8 same region\$4)	USPAT;	2004/08/31 22:29
			US-PGPUB;	•
			ЕРО; ЛРО;	
			DERWENT;	
			IBM_TDB	
-	1	20020042007.pn. and (evaluat\$4 same quality same pattern\$4)	USPAT;	2004/08/31 22:30
	1		US-PGPUB;	
			EPO; JPO;	
			DERWENT;	
			IBM_TDB	
1		20020042007	USPAT;	2004/09/01 22:38
-	2	20020042007.pn.		2004/09/01 22.36
		•	US-PGPUB;	
			ЕРО; ЛРО;	
			DERWENT;	
			IBM_TDB	
-	1	20020042007.pn. and mass.clm.	USPAT;	2004/09/01 23:01
,			US-PGPUB;	
			ЕРО; ЈРО;	
			DERWENT;	
			IBM_TDB	
_	1	20020042007.pn. and prior	USPĀT;	2004/09/01 23:08
	1	200200 1200 1.pm and prior	US-PGPUB;	
			ЕРО; ЛРО;	
			DERWENT;	
			IBM TDB	
	2727	DOM seem 2.1- min		2004/00/01 22:09
-	3736	ROM near3 logic	USPAT;	2004/09/01 23:08
			US-PGPUB;	
			ЕРО; ЛРО;	
			DERWENT;	
			IBM_TDB	
-	2193	ROM near2 logic	USPAT;	2004/09/01 23:10
	1		US-PGPUB;	
			ЕРО; ЛРО;	
			DERWENT;	
			IBM_TDB	
_	463	ROM near2 (logic near2 circuit)	USPAT;	2004/09/01 23:10
	103	Tools were (10010 month)	US-PGPUB;	
			EPO; JPO;	
			DERWENT;	
			IBM_TDB	2004/00/15 01 15
-	1	20020042007.pn. and (product\$4 near4 amount)	USPAT;	2004/09/16 01:15
	1		US-PGPUB;	
1			ЕРО; ЈРО;	
			DERWENT;	1
			IBM_TDB	

-	2	20020042007.pn.	USPAT;	2004/09/15 23:33
1			US-PGPUB;	
			EPO; JPO; DERWENT;	
}			IBM_TDB	
-	684	organic with (photomask\$3 or photo-mask\$3)	USPAT;	2004/09/16 00:24
	Í		US-PGPUB;	
)			ЕРО; ЛРО;	
			DERWENT;	
1	ł		IBM_TDB	
-	700	(mass near2 production) with (exposure or lithography)	USPAT;	2004/09/16 00:36
			US-PGPUB;	
1	ļ		EPO; JPO;	
			DERWENT; IBM_TDB	
-	5	((mass near2 production) with (exposure or lithography)) and	USPAT;	2004/09/16 00:26
		((100/121.ccls.)	US-PGPUB;	200 (70)/10 00:20
			ЕРО; ЈРО;	
}			DERWENT;	
			IBM_TDB	
-	355	organic\$4 with (photomask\$3 or photo-mask\$3 or mask\$3) with resin	USPAT;	2004/09/16 00:52
		with (photo or EUV or UV or ultra-violet or light or lightsource or	US-PGPUB;	
		photolithograph\$6 or photosensit\$6)	EPO; JPO;	
1			DERWENT; IBM_TDB	
_	1	(organic\$4 with (photomask\$3 or photo-mask\$3 or mask\$3) with resin	USPAT;	2004/09/16 00:48
İ	1	with (photo or EUV or UV or ultra-violet or light or lightsource or	US-PGPUB;	200 1103710 00.10
		photolithograph\$6 or photosensit\$6)) and (700/121.ccls.)	ЕРО; ЛРО;	
			DERWENT,	
1			IBM_TDB	
-	138	(organic\$4 with (photomask\$3 or photo-mask\$3 or mask\$3) with resin	USPAT;	2004/09/16 00:34
1	ļ	with (photo or EUV or UV or ultra-violet or light or lightsource or	US-PGPUB;	
}	J	photolithograph\$6 or photosensit\$6)) and (700/\$.ccls. or 702/\$.ccls. or	ЕРО; ЛРО;	
	1	438/\$.ccls. or 716/\$.ccls. or 430/\$.ccls.)	DERWENT; IBM_TDB	
_	1936	(mass near2 production) with (exposure or lithography or photomask\$3	USPAT;	2004/09/16 00:42
	1,20	or photo-mask\$3 or mask\$3 or resist or photo-resist or	US-PGPUB;	
		photolithograph\$6 or stepper)	ЕРО; ЈРО;	}
			DERWENT;	
1			IBM_TDB	
-	4	((organic\$4 with (photomask\$3 or photo-mask\$3) with resin	USPAT;	2004/09/16 00:46
		with (photo or EUV or UV or ultra-violet or light or lightsource or	US-PGPUB;	
1		photolithograph\$6 or photosensit\$6)) and (700/\$.ccls. or 702/\$.ccls. or 438/\$.ccls. or 716/\$.ccls. or 430/\$.ccls.)) and ((mass near2 production)	EPO; JPO; DERWENT;	
		with (exposure or lithography or photomask\$3 or photo-mask\$3 or	IBM_TDB	
		mask\$3 or resist or photo-resist or photolithograph\$6 or stepper))		
-	2805	(mass near2 (produc\$4 or manufactur\$4 or fabricat\$4 or making)) with	USPAT;	2004/09/16 00:46
		(exposure or lithograph\$6 or photomask\$3 or photo-mask\$3 or mask\$3	US-PGPUB;	
		or resist or photo-resist or photolithograph\$6 or stepper or	EPO; JPO;	
		photo-lithograph\$6)	DERWENT;	
	2806	(many nager) (nyadya\$4 ar manyfastya\$4 ar fak i sa\$4	IBM_TDB	2004/00/16 00:53
	2800	(mass near2 (produc\$4 or manufactur\$4 or fabricat\$4 or making)) with (exposur\$3 or lithograph\$6 or photomask\$3 or photo-mask\$3 or mask\$3	USPAT; US-PGPUB;	2004/09/16 00:52
		or resist or photo-resist or photolithograph\$6 or stepper or	EPO; JPO;	
		photo-lithograph\$6)	DERWENT;	
			IBM_TDB	
-	8	((organic\$4 with (photomask\$3 or photo-mask\$3 or mask\$3) with resin	USPAT;	2004/09/16 00:46
		with (photo or EUV or UV or ultra-violet or light or lightsource or	US-PGPUB;	
		photolithograph\$6 or photosensit\$6)) and (700/\$.ccls. or 702/\$.ccls. or	EPO; JPO;	
		438/\$.ccls. or 716/\$.ccls. or 430/\$.ccls.)) and ((mass near2 (produc\$4 or	DERWENT;	
		manufactur\$4 or fabricat\$4 or making)) with (exposur\$3 or lithograph\$6 or photomask\$3 or photo-mask\$3 or mask\$3 or resist or photo-resist or	IBM_TDB	
		photolithograph\$6 or stepper or photo-lithograph\$6))		
L		photomatographico or support or photo-reductaphico))	L	L

			13	
i -	13	((mass near2 (produc\$4 or manufactur\$4 or fabricat\$4 or making)) with	USPAT;	2004/09/16 00:48
		(exposur\$3 or lithograph\$6 or photomask\$3 or photo-mask\$3 or mask\$3	US-PGPUB;	
1	(or resist or photo-resist or photolithograph\$6 or stepper or	ЕРО; ЈРО;	
		photo-lithograph\$6)) and (700/121.ccls.)	DERWENT;	
			IBM_TDB	
-	76	(mass near2 (produc\$4 or manufactur\$4 or fabricat\$4 or making)) with	USPAT;	2004/09/16 00:56
		(before or prior) with (exposur\$3 or lithograph\$6 or photomask\$3 or	US-PGPUB;	
		photo-mask\$3 or mask\$3 or resist or photo-resist or photolithograph\$6	ЕРО; ЈРО;	
1		or stepper or photo-lithograph\$6)	DERWENT;	
			IBM_TDB	
-	276315	photomask\$3 or photo-mask\$3 or photoresist or photo-resist or ((mask\$3	USPAT;	2004/09/16 01:31
	ļ	or resist) with (photo or EUV or UV or ultra-violet or light or DUV or	US-PGPUB;	
	1	excimer or lightsource or photolithograph\$6 or photosensit\$6 or	ЕРО; ЈРО;	
		photo-lithograph\$6 or positive or negative))	DERWENT;	
			IBM TDB	
-	2	20020042007.pn. and (organic\$6)	USPAT;	2004/09/16 01:17
		(p)	US-PGPUB;	
			ЕРО; ЛРО;	
			DERWENT;	
			IBM TDB	
]_	9	("4684971" "5376483" "5378585" "5389474" "5418092" "5556724"	USPAT	2004/09/16 01:18
] -		"5741613" "5989760" "5948572").pn.	OSIAI	2004/07/10 01.18
	2110	((resist with (photo or EUV or UV or ultra-violet or light or DUV or	USPAT;	2004/09/16 01:32
-	2110		US-PGPUB;	2004/07/10 01:32
1		excimer or lightsource or photolithograph\$6 or photosensit\$6 or		
	i	photo-lithograph\$6 or positive or negative)) or photoresist) with	ЕРО; ЛРО;	
Į.		organic\$4 with resin	DERWENT;	
i i	107	/// '	IBM_TDB	2004/00/14 01 20
-	107	(((resist with (photo or EUV or UV or ultra-violet or light or DUV or	USPAT;	2004/09/16 01:39
1		excimer or lightsource or photolithograph\$6 or photosensit\$6 or	US-PGPUB;	
	{	photo-lithograph\$6 or positive or negative)) or photoresist) with	ЕРО; ЛРО;	
		organic\$4 with resin) and @py<1985	DERWENT;	
			IBM_TDB	
j -	228	(((resist with (photo or EUV or UV or ultra-violet or light or DUV or	USPAT;	2004/09/16 01:33
	ĺ	excimer or lightsource or photolithograph\$6 or photosensit\$6 or	US-PGPUB;	
		photo-lithograph\$6 or positive or negative)) or photoresist) with	ЕРО; ЈРО;	
		organic\$4 with resin).clm.	DERWENT;	
			IBM_TDB	1
-	14	((((resist with (photo or EUV or UV or ultra-violet or light or DUV or	USPAT;	2004/09/16 01:38
		excimer or lightsource or photolithograph\$6 or photosensit\$6 or	US-PGPUB;	
		photo-lithograph\$6 or positive or negative)) or photoresist) with	ЕРО; ЈРО;	
		organic\$4 with resin) and @py<1985) and ((((resist with (photo or EUV	DERWENT;	
		or UV or ultra-violet or light or DUV or excimer or lightsource or	IBM_TDB	
		photolithograph\$6 or photosensit\$6 or photo-lithograph\$6 or positive or	1	
		negative)) or photoresist) with organic\$4 with resin).clm.)		
-	4649	photoresist near2 metal	USPAT;	2004/09/16 01:39
			US-PGPUB;	
			ЕРО; ЈРО;	
}			DERWENT,	
			IBM_TDB	
-	680	(photoresist near2 metal).clm.	USPĀT;	2004/09/16 01:39
		·	US-PGPUB;	
	}		ЕРО; ЈРО;	
			DERWENT;	
1	1		IBM TDB	
-	75	((photoresist near2 metal).clm.) and @py<1985	USPAT;	2004/09/16 14:41
1		We will be a second of the sec	US-PGPUB;	
			EPO; JPO;	
1	1		DERWENT;	
			IBM_TDB	
	<u> </u>		ממד דאוריי	L

-	0	20020042007.pn. and (Rom same logic same cell)	USPAT;	2004/09/16 19:26
		,	US-PGPUB;	
			ЕРО; ЈРО;	
			DERWENT;	
			IBM_TDB	,
-	1	5965306.pn. and (mass with production)	USPAT,	2004/09/16 20:44
			US-PGPUB;	
			ЕРО; ЛРО;	
			DERWENT;	
	:		IBM_TDB	
-	2	5965306.pn.	USPAT;	2004/09/16 20:44
			US-PGPUB;	
			ЕРО; ЈРО;	
			DERWENT;	
			IBM_TDB	
-	2241	(mass near2 (produc\$4 or manufactur\$4 or fabricat\$4 or making)) with	USPAT;	2004/09/16 21:26
		(deposit\$4 or anneal\$5)	US-PGPUB;	
			EPO; JPO;	
			DERWENT;	
			IBM_TDB_	